Hiroshi Fukuda

List of Publications by Year
in descending order

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28	457	11	17
papers	citations	h-index	g-index

840776 888059

28	28	28	172
all docs	docs citations	times ranked	citing authors

#	Article	IF	Citations
1	Cascade and cluster of correlated reactions as causes of stochastic defects in extreme ultraviolet lithography. Journal of Micro/ Nanolithography, MEMS, and MOEMS, 2020, 19, 1.	0.9	6
2	Dissolution nonlinearity tail degradation with decreased reaction events impacts EUV stochastic defect generations. , 2020, , .		2
3	Localized and cascading secondary electron generation as causes of stochastic defects in extreme ultraviolet projection lithography. Journal of Micro/ Nanolithography, MEMS, and MOEMS, 2019, 18, 1.	0.9	9
4	Impact of asymmetrically localized and cascading secondary electron generation on stochastic defects in EUV lithography. , 2019, , .		3
5	Estimating extremely low probability of stochastic defect in extreme ultraviolet lithography from critical dimension distribution measurement. Journal of Micro/ Nanolithography, MEMS, and MOEMS, 2019, 18, 1.	0.9	4
6	Stochastic defect generation in EUV lithography analyzed by spatially correlated probability model, reaction-limited and scattering-limited?. , 2019, , .		2
7	Measurement of pattern roughness and local size variation using CD-SEM. Journal of Micro/ Nanolithography, MEMS, and MOEMS, 2018, 17, 1.	0.9	5
8	Measurement of pattern roughness and local size variation using CD-SEM: current status. , 2018, , .		3
9	Cross-sectional profile prediction from top-view SEM images based on root-cause decomposition of line-edge roughness. Proceedings of SPIE, 2014, , .	0.8	0
10	Performance Limitation of Microwave Assisted Magnetic Recording Combined With Exchange Coupled Composite Media Explored by Genetic Algorithm. IEEE Transactions on Magnetics, 2013, 49, 3640-3643.	2.1	3
11	Root-cause decomposition of line edge roughness and its application to cross-section profile prediction using top-view SEM images. Journal of Vacuum Science and Technology B:Nanotechnology and Microelectronics, 2013, 31, 06F802.	1.2	0
12	Recording Density Limitation Explored by Head/Media Co-Optimization Using Genetic Algorithm and GPU-Accelerated LLG. IEEE Transactions on Magnetics, 2012, 48, 3895-3898.	2.1	9
13	LER evaluation of molecular resist for EUV lithography. Microelectronic Engineering, 2007, 84, 1084-1087.	2.4	12
14	Molecular resists based on cholate derivatives for electron-beam lithography. , 2006, 6153, 762.		8
15	Depth profile and line-edge roughness of partiallyO-1-ethoxyethylated low molecular weight amorphous polyphenol and poly(p-hydroxystyrene) base resists for electron-beam lithography. Polymers for Advanced Technologies, 2006, 17, 116-121.	3.2	19
16	Molecular Resists Based on Cholate Derivatives for Electron-Beam Lithography. Japanese Journal of Applied Physics, 2006, 45, 5435-5439.	1.5	11
17	Depth Profile and Line-Edge Roughness of Low-Molecular-Weight Amorphous Electron Beam Resists. Japanese Journal of Applied Physics, 2005, 44, 5484-5488.	1.5	36
18	Impact of Long-Period Line-Edge Roughness (LER) on Accuracy in Critical Dimension (CD) Measurement and New Guideline for CD Metrology. Japanese Journal of Applied Physics, 2005, 44, 5575-5580.	1.5	26

#	Article	IF	Citations
19	Spectral analysis of line-edge roughness in polyphenol EB-resists and its impact on transistor performance. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 2005, 23, 2711.	1.6	43
20	Metrology of LER: influence of line-edge roughness (LER) on transistor performance. , 2004, , .		32
21	Analysis of Line Edge Roughness Using Probability Process Model for Chemically Amplified Resists. Japanese Journal of Applied Physics, 2003, 42, 3748-3754.	1.5	39
22	Characterization of line-edge roughness in resist patterns and estimations of its effect on device performance. , 2003, 5038, 689.		45
23	Analysis of Line-edge Roughness in Resist Patterns and Its Transferability as Origins of Device Performance Degradation and Variation. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2003, 16, 387-393.	0.3	22
24	Auxiliary pattern generation to cancel unexpected images at sidelobe overlap regions in attenuated phase-shift masks. , 1999, , .		0
25	Fabrication of silicon nanopillars containing polycrystalline silicon/insulator multilayer structures. Applied Physics Letters, 1997, 70, 333-335.	3.3	23
26	<title>Effects of radially nonsymmetric pupil filters and multiple-pupil exposure</title>. , 1996, 2726, 375.		2
27	Evaluation of Pupil-Filtering in High-Numerical Aperture I-Line Lens. Japanese Journal of Applied Physics, 1993, 32, 5845-5849.	1.5	13
28	Imaging Characteristics of Multi-Phase-Shifting and Halftone Phase-Shifting Masks. Japanese Journal of Applied Physics, 1991, 30, 2991-2997.	1.5	80